

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau



(43) International Publication Date
21 October 2010 (21.10.2010)

(10) International Publication Number
WO 2010/119263 A1

PCT

(51) International Patent Classification:

C08F 2/48 (2006.01) **C08F 2/54** (2006.01)
C08F 2/52 (2006.01) **C08J 3/24** (2006.01)
B05D 7/24 (2006.01) **C08J 3/28** (2006.01)
B29C 59/14 (2006.01) **C23C 16/00** (2006.01)

(21) International Application Number:

PCT/GB2010/000772

(22) International Filing Date:

16 April 2010 (16.04.2010)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

0906680.4 17 April 2009 (17.04.2009) GB

(71) Applicant (for all designated States except US): **SURREY NANOSYSTEMS LIMITED** [GB/GB]; Euro Business Park, Newhaven, East Sussex (GB).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **SILVA, Sembukutiarachilage, Ravi, Pradip** [GB/GB]; 29 Verran Road, Camberley, Surrey GU15 2ND (GB). **ESTEFANIA, José, Virgilio, Anguita, Rodriguez** [GB/GB]; 9 Coltsfoot Place, Hook, Hampshire, RG27 9PW (GB).

(74) Agents: **TOLLETT, Ian** et al.; Williams Powell, Staple Court, 11 Staple Inn Buildings, London, WC1V 7QH (GB).

(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

- with international search report (Art. 21(3))
- before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments (Rule 48.2(h))

(54) Title: MATERIAL HAVING A LOW DIELECTRIC KONSTANT AND METHOD OF MAKING THE SAME

(57) Abstract: There is disclosed a method for producing a highly cross-linked polypropylene material by plasma polymerisation of a carbon containing gas, not specifically propylene, exhibiting low relative permittivity, high thermal stability and enhanced mechanical properties, said method and material being suitable for application not limited to interlayer dielectric deposition in microchip fabrication.



WO 2010/119263 A1